

Influence of Excited States of Deep Acceptors on Hole Concentration in SiC

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Experimental acceptor levels ΔE_A in SiC, measured from the valence band E_V , are reported to be deeper than 150 meV. Moreover, the ground and first excited state levels of acceptors in SiC, calculated by hydrogenic acceptor [$\Delta E_r = 13.6(m^*/\epsilon_s^2 r^2)$ eV], are 136 meV and 34 meV, respectively. The experimental ΔE_A is deeper than ΔE_1 because of central cell corrections, while ΔE_r ($r \geq 2$) are considered to be reasonable, and should affect the hole concentration $p(T)$. Using three kinds of distribution functions, we theoretically and experimentally investigate the influence of the excited states on $p(T)$.

The proposed distribution function for electrons is expressed as

$$f(\Delta E_A, n, \overline{E_{ex}}) = \frac{1}{1 + 4 \exp\left(-\frac{\overline{E_{ex}}}{kT}\right) \cdot \left\{ g_1 \exp\left(\frac{\Delta E_A - \Delta E_F}{kT}\right) + \sum_{r=2}^n g_r \exp\left(\frac{\Delta E_r - \Delta E_F}{kT}\right) \right\}}, \quad (1)$$

where ΔE_F is the Fermi level measured from E_V , g_r is the $(r-1)$ -th excited state degeneracy factor, and n is the highest excited state, which we consider in analysis. Here, the average acceptor level $\overline{\Delta E_A}$ is expressed as $\overline{\Delta E_A} = \Delta E_A - E_{ex}$, and E_{ex} is the ensemble average of the ground and excited state levels, which increases with T . The Fermi-Dirac distribution function corresponds to $f(\Delta E_A, 1, 0)$ and the conventional function is $f(\Delta E_A, n, 0)$.

Using p-type 6H-SiC wafer, $p(T)$ was obtained by Hall-effect measurements. Using Free Carrier Concentration Spectroscopy (FCCS), ΔE_A , the acceptor density N_A and the compensating density N_{com} were determined, and are shown in Table 1. Figure 1 shows the $p(T) - 1/T$ curves, and Fig. 2 displays the FCCS curve given by $H(T, E_{ref}) \equiv p(T)^2 \exp(E_{ref}/kT)/(kT)^{5/2}$, where the simulation results mean the curves simulated using Table 1.

In $f(\Delta E_A, 1, 0)$, although the simulated $p(T)$ is in agreement with the experimental $p(T)$, the simulated $H(T, E_{ref})$ is not, indicating that the excited states should affect $p(T)$. In $f(\Delta E_A, n, 0)$, the density of holes bound to acceptors increases, which results in the unreasonable high N_A . In our case, there are good coincidences between the experimental data and simulation results in Fig. 1 as well as in Fig. 2, and N_A and ΔE_A are considered to be reasonable.

In summary, the influence of the excited states on $p(T)$ should be considered, and the distribution function used in deep acceptors should be $f(\Delta E_A, n, \overline{E_{ex}})$.

Table 1 Results determined by FCCS

	$f(\Delta E_A, 1, 0)$	$f(\Delta E_A, 10, 0)$	$f(\Delta E_A, 10, \overline{E_{ex}})$
N_A [cm^{-3}]	2.95×10^{19}	2.19×10^{20}	1.91×10^{18}
ΔE_A [meV]	182	205	189
N_{com} [cm^{-3}]	8.35×10^{17}	2.65×10^{18}	3.37×10^{16}

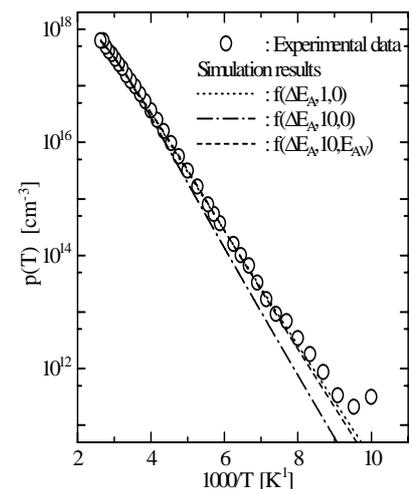


Fig. 1 Experimental and simulation results of $p(T)$

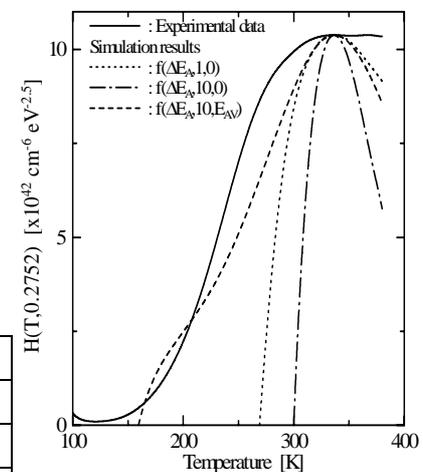


Fig. 2 Experimental and simulation results of $H(T, E_{ref})$